



Attorney Docket No.: 02SPE113P-DIV2

GP 2822

H61A
12/19/02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Hsia, et al.

Serial No.: 09/955,677

Filed: September 19, 2001

For: **Method and Apparatus for High-Resolution In-Situ Plasma Etching of Inorganic and Metal Films**

Art Unit: 2822

Examiner: Ida M. Soward

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AMENDMENT AND RESPONSE TO OFFICE ACTION

Honorable Commissioner of
Patents and Trademarks
Washington, D.C. 20231

Dear Sir/Madam:

This is in response to the Office Action dated September 26, 2002 in the above-referenced patent application. Please enter and consider the following amendments and remarks.

Please change the Attorney Docket No. in this application from "050324-1141" to --02SPE113P-DIV2--.

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